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(54) Title: CLEANING AGENT COMPOSITION, CLEANING AND PRODUCTION METHODS FOR SEMICONDUCTOR WAFER, AND SEMICONDUCTOR WAFER

(57) Abstract: A cleaning agent composition comprising a nonionic surfactant represented by the following formula (I):  $R1O(EO)_x(PO)_yH$  (I) (wherein R1 represents a linear or branched alkyl group having from 6 to 20 carbon atoms or a linear or branched alkenyl group having from 6 to 20 carbon atoms, EO represents an oxyethylene group, PO represents an oxypropylene group, EO and PO each is bonded by random addition or block addition, x number of EO's and y number of PO's are arranged in an arbitrary order, x and y each independently represents an integer of 1 to 20, and  $x/(x+y)$  is 0.5 or more) and a quaternary ammonium hydroxide is provided. Also, Cleaning and production methods for semiconductor wafer using the cleaning agent composition, and semiconductor wafer produced by the production method are provided.



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